

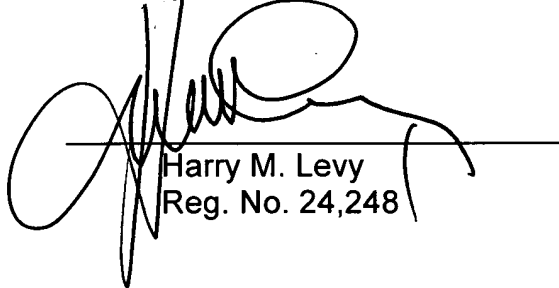
the barrier layer of the Onabe et al. publication US 2003/0134749 (now U.S. Patent No. 6,743,531) and concluded that the Examiner is incorrect in her calculations. Following Dr. Balachandran's example in the enclosed Declaration, the correct atom percents in the diffusion layer are not as calculated by the Examiner, but are in excess of 60 atom percent copper rather than the 0.1 to 0.3 atom percent set forth in the subject application and the claims at issue. Because the Examiner incorrectly calculated the copper percent, it is submitted that all the claims as now presented are drawn to patentable subject matter in view of the Onabe et al. reference and the allowance thereof is requested.

Also enclosed is a shortened version of Dr. Balachandran's curriculum vitae.

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Respectfully submitted,

Emrich & Dithmar, LLC.
Attorneys for Applicants



Harry M. Levy
Reg. No. 24,248

125 South Wacker Drive
Suite 2080
Chicago, Illinois 60606
Phone: (312)-663-9800
Facsimile: (312) 663-9822
e-mail: Emrichhml@aol.com